

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Appln. of: Hin-Yiu Chung ET AL.
 Appln. No.: Not yet assigned
 Filed: Herewith
 For: METHOD FOR OXIDIZING A
 LAYER, AND ASSOCIATED
 HOLDING DEVICES FOR A
 SUBSTRATE

Examiner: Not yet assigned

Art Unit: N/A

Attorney Docket No: 10808/200

#2

INFORMATION DISCLOSURE STATEMENT

In accordance with the duty of disclosure under 37 C.F.R. §1.56 and §§1.97-1.98, and more particularly in accordance with 37 C.F.R. §1.97(b), Applicants hereby cite the following reference(s):

No.	Date of Publication	Patentee/Applicant/Assignee
US 2002/0026900 A1	March 7, 2002	Huang et al.
6,342,691 B1	January 29, 2002	Johnsgard et al.
5,872,889	February 16, 1999	Kaltenbrunner et al.
5,635,409	June 3, 1997	Meslehi
5,581,571	December 3, 1996	Holonyak, Jr. et al.
5,385,866	January 31, 1995	Bartush
5,313,044	May 17, 1994	Massoud et al.
FOREIGN PATENT DOCUMENTS		
DOCUMENT NUMBER	DATE	COUNTRY
GB 2 355 850 A	May 2, 2001	United Kingdom
WO 99/03141	January 21, 1999	WO
GB 2 295 271 A	May 22, 1996	United Kingdom
DE 689 19 408 T2	September 29, 1989	Germany
DE 37 50 382 T2	March 4, 1987	Germany
OTHER ART – NON PATENT LITERATURE DOCUMENTS		
Spezialgraphite von SGL Carbon, Produkte für die Halbleitertechnik, SGL Carbon Group, pgs. 2-17,		
H.Q. Jia, H. Chen, W.C. Wang, W.X. Wang, W. Li, Q. Huang and Jiunming Zhou, <i>The Study of Thermal Stability During Wet Oxidation of AIAS</i> , Institute of Physics, Chinese Academy of Sciences, pgs. 484-488, Journal of Crystal Growth, Vol. 223, Issue 4, March 2001.		
William G. Breiland, Michael E. Coltrin, J. Randall Creighton, Hong Q. Hou, Harry K. Moffat and Jeffrey Y. Tsao, <i>Organometallic Vapor Phase Epitaxy</i> , Center for Compound Semiconductor Science and Technology, Sandia National Laboratories, Materials Science and Engineering: R. Reports, Vol. 24, Issue 6, pgs. 241-274, February 1999.		
Copy of International Search Report from International Application Number PCT/DE/02523.		
Copy of Examination Report from International Application Number PCT/DE/02523.		

10/522505
DT01 Rec'd PCT/PTO 26 JAN 2005

Applicants are enclosing Form PTO-1449 (one sheet), along with a copy of each listed reference for which a copy is required under 37 C.F.R. §1.98(a)(2). As each of the listed references is in English, no further commentary is believed to be necessary, 37 C.F.R. §1.98(a)(3). Applicants respectfully request the Examiner's consideration of the above reference(s) and entry thereof into the record of this application.


By submitting this Statement, Applicants are attempting to fully comply with the duty of candor and good faith mandated by 37 C.F.R. §1.56. As such, this Statement is not intended to constitute an admission that any of the enclosed references, or other information referred to therein, constitutes "prior art" or is otherwise "material to patentability," as that phrase is defined in 37 C.F.R. §1.56(a).

Applicants have calculated no fee to be due in connection with the filing of this Statement. However, the Director is authorized to charge any fee deficiency associated with the filing of this Statement to a deposit account, as authorized in the Transmittal accompanying this Statement.

Respectfully submitted,

1/20/05

Date



Anthony P. Curtis, Ph.D.
(Reg. No. 46,193)

10/522505
 DTOT Rec'd PCT/PT 26 JAN 2005

FORM PTO-1449	SERIAL NO. Not yet assigned	CASE NO. 10808/200
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)	FILING DATE Herewith	GROUP ART UNIT Not yet assigned
APPLICANT(S): Hin-Yiu Chung et al.		

REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
	A1	US 2002/0026900 A1	March 7, 2002	Huang et al.		
	A2	6,342,691 B1	January 29, 2002	Johnsgard et al.		
	A3	5,872,889	February 16, 1999	Kaltenbrunner et al.		
	A4	5,635,409	June 3, 1997	Meslehi		
	A5	5,581,571	December 3, 1996	Holonyak, Jr. et al.		
	A6	5,385,866	January 31, 1995	Bartush		
	A7	5,313,044	May 17, 1994	Massoud et al.		

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
	A8	GB 2 355 850 A	May 2, 2001	United Kingdom		
	A9	WO 99/03141	January 21, 1999	WO		
	A10	GB 2 295 271 A	May 22, 1996	United Kingdom		
	A11	DE 689 19 408 T2	September 29, 1989	Germany		
	A12	DE 37 50 382 T2	March 4, 1987	Germany		

OTHER ART - NON PATENT LITERATURE DOCUMENTS

EXAMINER INITIAL		(Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.
	A13	Spezialgraphite von SGL Carbon, Produkte für die Halbleitertechnik, SGL Carbon Group, pgs. 2-17,
	A14	H.Q. Jia, H. Chen, W.C. Wang, W.X. Wang, W. Li, Q. Huang and Jiunming Zhou, <i>The Study of Thermal Stability During Wet Oxidation of AlAs</i> , Institute of Physics, Chinese Academy of Sciences, pgs. 484-488, Journal of Crystal Growth, Vol. 223, Issue 4, March 2001.
	A15	William G. Breiland, Michael E. Coltrin, J. Randall Creighton, Hong Q. Hou, Harry K. Moffat and Jeffrey Y. Tsao, <i>Organometallic Vapor Phase Epitaxy</i> , Center for Compound Semiconductor Science and Technology, Sandia National Laboratories, Materials Science and Engineering: R. Reports, Vol. 24, Issue 6, pgs. 241-274, February 1999.
	A16	Copy of International Search Report from International Application Number PCT/DE/02523.
	A17	Copy of Examination Report from International Application Number PCT/DE/02523.

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.